Amendments to the Claims:

The following listing of claims will replace all prior versions, and listings, of claims in the application:

- 1-6. (Cancelled).
- 7. (Currently Amended) A semiconductor device, comprising:

 a substrate including a plurality of holes and a surface over which an
 interconnecting pattern is formed, part of the interconnecting pattern being superposed over
 the holes;

a semiconductor chip disposed over another surface of the substrate and including a plurality of electrodes to be positioned over the holes; and

conductive members provided within the holes for electrically connecting the electrodes to the interconnecting pattern,

— wherein a recognition hole is-formed in the substrate at a position differing from the holes; and

— wherein a recognition pattern is-formed over the recognition hole on the side of a surface of the substrate including the interconnecting pattern.

8. (Currently Amended) The semiconductor device as defined in claim 7,

— wherein the recognition hole is formed in the substrate outside a mounting

9. (Currently Amended) The semiconductor device as defined in claim 7,
 —————wherein the recognition pattern includes:

a first pattern extending in the X-axis direction of the two-dimensional coordinate system established on a surface of the substrate; and

a second pattern extending in the Y-axis direction.

10-12. (Cancelled).

region for the semiconductor chip.

13.	(Currently Amended) A semiconductor device, comprising:
-	a substrate including a plurality of holes and a surface over which an
interconnecting pattern is formed, part of the interconnecting pattern being superposed over	
the holes;	
	a semiconductor chip disposed over another surface of the substrate and
including a plurality of electrodes to be positioned over the holes; and	
	conductive members provided within the holes for electrically connecting the
electrodes to the interconnecting pattern,	
	wherein the conductive members are a plurality of layered bumps,
	wherein the bumps include first bumps formed on the electrodes and second
bumps formed on the first bumps, and	
	wherein the second bumps are formed of a metal which has a melting point
lower than the melting point of the first bumps.	
14.	(Currently Amended) The semiconductor device as defined in claim 13,
	wherein the first bumps are formed of gold.
15.	(Currently Amended) The semiconductor device as defined in claim 14,
	wherein the second bumps are formed of solder.
16-33	(Cancelled).